

11th Korean ALD Workshop Program

(2015. 04. 24)

시 간	일 정	발 표 자
9:00~9:10	제 11차 Korean ALD Workshop 개최식	
9:10~9:50	Atomic Layer Deposition of Titanium Metal and Other Electropositive Element Films	Chuck Winter (Wayne State University)
9:50~10:30	Progress and challenges of ALD/CVD precursor development	고원용 (UP chem)
10:30~11:00	Coffee Break	
11:00~11:40	Synthesis of novel metal-organic complexes and their application in atomic layer deposition	한정환 (한국화학연구원)
11:40~12:20	Atomic layer deposition for low-temperature thin film SOFC application	김영범 (한양대)
12:20 ~ 14:00	점심 식사 (생활과학관 7층)	
14:00~14:40	Application of PEALD to the high mobility oxide TFT	박상희 (KAIST)
14:40~15:20	Atomic layer deposition of amorphous molybdenum sulfide for electrochemical hydrogen evolution catalysis	민요셉 (건국대)
15:20~15:50	Coffee Break	
15:50~16:30	ALD for high volume manufacturing: Latest trends, developments, and market applications	Adrien LaVoie (Lam research)
16:30~17:10	최근 DRAM 공정에서 사용되는 ALD 공정	이정엽 (SK hynix)
17:10~17:50	Effects of Interfacial Layer on Characteristics of TiN/ZrO ₂ Structures	김윤수 (삼성전자)
	한국 ALD workshop 기록	전형탁 (Hanyang Univ.)